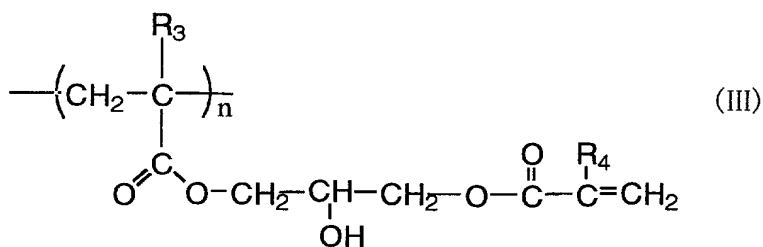
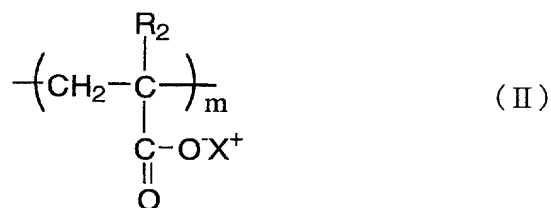
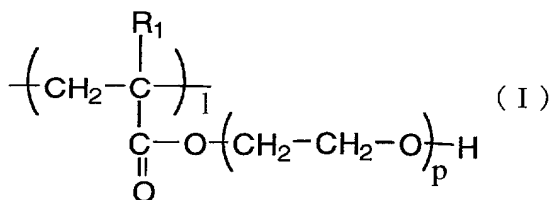
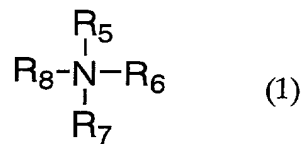


ABSTRACT OF THE DISCLOSURE

The present invention provides a cross-linkable polymer compound which can be developed with an aqueous developer and exhibits excellent patterning properties; a photosensitive composition containing the same; and a pattern formation method employing the composition. The polymer compound containing monomer units represented by formulas (I) to (III):



wherein each of R₁ to R₄ is hydrogen and/or a methyl group; p represents an integer between 1 to 10 inclusive; X represents hydrogen, an alkali metal, or an ammonium represented by formula (1):



wherein each of R_5 to R_8 represents hydrogen, a C1-C3 alkyl group, or a C1-C3 alkanol group; and a plurality of Xs may be the same or different from one another, the compositional proportions of the monomer units falling within the following ranges: $2 \text{ mol\%} \leq l \leq 73 \text{ mol\%}$; $8 \text{ mol\%} \leq m \leq 83 \text{ mol\%}$; and $15 \text{ mol\%} \leq n \leq 80 \text{ mol\%}$.